

Amendments to the Specification:

On pp. 41-42, please replace the paragraph, p. 41, lines 27-30 – p. 42, lines 1-7 with the following amended paragraph:

---In an experiment to demonstrate that the presence of *in situ* synthesised oligodeoxynucleotides on a surface would not compromise the ability of that surface to hold a charge pattern, images were formed on glass surfaces on which had been synthesised oligodeoxynucleotides comprising (dT)₁₂ (SEQ ID NO:1) and (dT)₂₅ (SEQ ID NO:1). Glass coverslips (24mm x 50mm x 0.13mm) were sandwiched into a reaction chamber comprising a front of PerspexTM and a back of polypropylene. The volume of the chamber (0.2ml to 0.4ml) was defined by gaskets cut from silicon rubber sheet with holes machined through the polypropylene to enable entry and exit of reagents. Entry and exit ports were designed so that the reaction block could be fitted in-line in an Applied Biosystems 394 DNA/RNA synthesiser, in place of a standard oligo-synthesis column.---

On page 42, please replace the paragraph, lines 9 -17 with the following amended paragraph:

---Coverslips were cleaned in a solution containing 0.1% PyronegTM, 1% NaOH and 10% ethanol, rinsed exhaustively with Milli QTM water, before being dried at 110 degrees C immediately prior to use. For synthesis of a silane chemically functional layer, coverslips were immersed in a solution of 5% v/v glycidoxypyril trimethoxysilane in toluene for 30 minutes at room temperature, rinsed with toluene and baked at 110 degrees C for 30 minutes. The glycidoxy ring was opened to facilitate reaction with phosphoramidites by incubation in 0.5M HCl for 30 minutes. Once in the reaction chamber, coverslip surfaces were subjected to standard synthesis cycles of the ABI 394 for synthesis of (dT)₁₂ (SEQ ID NO:1) and (dT)₂₅ (SEQ ID NO:1).---

On page 42, please replace the paragraph at lines 19-24 with the following amended paragraph:

---On removal from the reaction chamber charge patterns were formed on the coverslips using a single point corona and mask and the charge patterns were developed using a particulate electrostatic liquid toner. The presence of strong images in the regions on which the (dT)₁₂ (SEQ ID NO:1) and (dT)₂₅ (SEQ ID NO:1) oligomers had been synthesised confirmed that their presence did not compromise the ability of the dielectric surface to hold a charge pattern.---